

Application No. 10/027,906

AMENDMENTS TO THE SPECIFICATION

In the Specification

Please substitute the following amended paragraph(s) and/or section(s) (deleted matter is shown by strikethrough and added matter is shown by underlining):

At page 55, lines 17-25, please replace the paragraph with the following. Note that this paragraph was previously amended in the Amendment of March 31, 2004.

With respect to specific examples, the production of silicon oxide nanoparticles is described in copending and commonly assigned U.S. Patent Application Serial Number 09/085,514, now U.S. Patent 6,726,990 to Kumar et al., entitled "Silicon Oxide Particles," incorporated herein by reference. This patent application describes the production of amorphous SiO<sub>2</sub>. The production of titanium oxide nanoparticles and crystalline silicon dioxide nanoparticles is described in copending and commonly assigned, U.S. Patent Application Serial Number 09/123,255, now U.S. Patent 6,387,531 to Bi et al., entitled "Metal (Silicon) Oxide/Carbon Composites," incorporated herein by reference. In particular, this application describes the production of anatase and rutile TiO<sub>2</sub>.

At page 69, line 26 to page 70, line 8, please replace the paragraph with the following:

Generally, light reactive deposition involves the deposition of materials onto a substrate. However, it has been discovered that a release layer can be formed such that separation at the release layer separates an optical structure from the substrate on which it was formed. The release layer generally comprises powders with significantly higher flow temperatures than the materials deposited above. The composition of the powder can change gradually or abruptly from one

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composition to another by adjusting the precursor composition in the deposition apparatus. Conditions and compositions can be selected to produce a desirable segregation such that a release layer is formed upon heat treatment. Alternatively, the release layer can be formed by a thermal exposure from the top to consolidate only a portion of the thickness of material, leaving the release layer intact. Formation of release layers and the use of release layers to form substrateless optical structures is described further in copending and commonly assigned U.S. Patent Application serial number 09/931,977, now U.S. Patent 6,788,866 to Bryan, entitled "Layer Materials On Substrates," incorporated herein by reference.